Icemos Technology Ltd Product Specification 1003.260502 Issue Date 04 February 2020 15:0

Part Number	Customer	

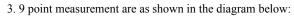
Category	Parameter		Specification	Measurement Method
OverallWafer	1.0	Diameter	150.00 +/- 0.50 mm	WaferVendor
	2.0	Primary Flat Length	57.50 +/- 2.50 mm	Wafer Vendor
	3.0	Primary Flat Orientation	{110}+/- 0.5 degree	Wafer Vendor
	4.0	Growth Method	CZ	Wafer Vendor
	5.0	Туре	Р	Wafer Vendor
	6.0	Dopant	Boron	Wafer Vendor
	7.0	Resistivity	10~30 ohm cm	Wafer Vendor
	8.0	Overall Thickness	1,100.00 +/- 25.00 um	Wafer Vendor
	9.0	Total Thickness Variation (TTV)	<10.00um	Guaranteed by process
	10.0	Orientation	<100> +/-0.5	Wafer Vendor
	11.0	Back Surface Quality	Lapped/Etched	Wafer Vendor
	12.0	Front Surface Quality	Prime	Wafer Vendor
	13.0	Edge Chips	None	Bright Light 100% (note 2)
DeviceSilicon	15.0		None	Bright Light, 100% (note 2).
	16.0	Scratches	None	Bright Light, 100% (note 2).

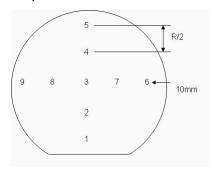
Page 1 of 2 10/03/2020 www.icemostech.com

Part Number		Customer	
Category	Parameter	Specification	Measurement Method
Shipping Details	Wafer per box :	Max 25	
	Packaging:	Taped Polypropylene Wafer Box Empak, Ultrapak, 150.00mm Antistatic Double Bagging	
	Lot Shipment Data	Device Thickness Bow / Warp Data Handle and SOI Thickness	
Explanatory Notes	1. Microscope inspec	tion performed using microscope scan as below. 5x objective.	
		pections performed exclude all wafer area outside the edge exclusio	on defined in Overall

2. All bright light inspections performed exclude all wafer area outside the edge exclusion defined in Overall Wafer, Edge Exclusion. High intensity bright lamp inspection as per ASTM F523.

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Additional Information